

Page 24, line 6, please insert --be-- after "may".

IN THE CLAIMS:

Please amend claims 3-12, and 16, and add new claim 21 as follows. Note that claims 1, 2, 4, and 17-20 remain unamended, but are reproduced below for the Examiner's convenience and reference.

1                   1.     A method of removing residue from a substrate processing chamber,  
2     said method comprising the steps of:  
3                   forming a plasma remotely with respect to said chamber, said plasma including  
4     a plurality of reactive radicals;  
5                   forming a flow of said reactive radicals traversing toward said chamber;  
6                   forming a diluent gas flow;  
7                   mixing said flow of said reactive radicals and said diluent gas flow anterior to  
8     said chamber to form a gas-radical mixture; and  
9                   flowing said gas-radical mixture into said chamber.

1                   2.     The method as recited in claim 1 wherein said flow of reactive radicals  
2     and said gas flow are established to maintain a pressure within said chamber below one torr.

1                   3.     (Amended) The method as recited in claim 1 wherein said reactive  
2     radicals comprise [of the] atoms associated with a reactive gas, with said reactive gas being  
3     selected from a group consisting of  $\text{NF}_3$ , dilute  $\text{F}_2$ ,  $\text{CF}_4$ ,  $\text{C}_2\text{F}_6$ ,  $\text{C}_3\text{F}_8$ ,  $\text{SF}_6$ , and  $\text{ClF}_3$ .

1                   4.     (Amended) The method as recited in claim 1 wherein said diluent gas  
2     flow comprises a[n] inert gas.

1                   5.     (Amended) The method as recited in claim 1 wherein said diluent gas  
2     flow comprises [of] a reduction gas.

1                   6.     (Amended) The method as recited in claim 1 wherein said chamber has  
2     components therein, with a subset of said radicals in said gas-radical mixture reacting with said

3 components creating a residue and further including the step of exhausting said residue, with a  
4 rate at which said residue is exhausted [is] depending upon a rate of said diluent gas flow.

1 7. (Amended) The method as recited in claim 1 wherein said diluent gas  
2 flow travels at a first rate and said flow of said reactive radicals travel at a second rate with a  
3 ratio of said first rate to said second rate being at least 2:1.

1 8. (Amended) A substrate processing apparatus having a process chamber,  
2 said apparatus, comprising:

3 means for forming a plasma remotely with respect to said chamber, said plasma  
4 including a plurality of reactive radicals;

5 means, in fluid communication with said means for forming a plasma, for  
6 forming a flow of said reactive radicals traversing toward said chamber;

7 means[, in fluid communication with said means for forming a plasma,] for  
8 forming a diluent gas flow;

9 means, in fluid communication with said means for forming a [plasma] flow of  
10 said reactive radicals and with said means for forming a diluent gas flow, for mixing said flow  
11 of said reactive radicals and said diluent gas flow downstream of said means for forming a  
12 plasma and anterior to said chamber to form a gas-radical mixture; and

13 means, in fluid communication with said means for [forming a plasma]  
14 mixing, for flowing said gas-radical mixture into said chamber.

1 9. (Amended) The apparatus as recited in claim 8 wherein said means for  
2 forming a diluent gas flow includes a supply of diluent gas and a pump system in fluid  
3 communication therewith, with said supply of diluent gas comprising a[n] nonplasma inert gas.

1 10. (Amended) The apparatus as recited in claim 8 wherein said diluent gas  
2 flow travels at a first rate and said flow of said reactive radicals travel at a second rate with a  
3 ratio of said first rate to said second rate being at least 2:1.

1 11. (Amended) The apparatus as recited in claim 9 wherein said supply of  
2 diluent gas comprises [of] a reducing gas.

1 12. (Amended) The apparatus as recited in claim 8 wherein said means for  
2 forming a plasma includes a plasma applicator defining an internal volume and a supply of  
3 reactive gas in fluid communication with said internal volume, with said supply of reactive gas  
4 being selected from a group consisting of NF<sub>3</sub>, dilute F<sub>2</sub>, CF<sub>4</sub>, C<sub>2</sub>F<sub>6</sub>, C<sub>3</sub>F<sub>8</sub>, SF<sub>6</sub>, and [C<sub>1</sub>F<sub>3</sub>]  
5 ClF<sub>3</sub>.

1 13. The apparatus as recited in claim 12 wherein said plasma applicator  
2 includes a microwave source in electrical communication with said plasma applicator.

1 14. The apparatus as recited in claim 9 wherein said pump system maintains  
2 a pressure within said chamber below one torr.

1 15. The apparatus as recited in claim 9 wherein said inert gas is argon.

1 16. (Amended) A[n] substrate processing apparatus, comprising:  
2 a processing chamber having an intake port;  
3 a supply of diluent gas;  
4 a plasma source for generating a plasma consisting of reactive radicals, said  
5 plasma source including a conductive plasma applicator defining an internal volume, said  
6 applicator having an input aperture and an output aperture, each of which is equipped with  
7 microwave arrestors;  
8 a [fluid] mixing manifold having multiple inlets and an outlet with said outlet  
9 being coupled to said intake port and one of said inlets being in fluid communication with said  
10 [gas] outlet aperture of said conductive plasma applicator, with the remaining inlets being in  
11 fluid communication with said supply of diluent gas;  
12 a pump system, in fluid communication with both said plasma source and said  
13 supply of diluent gas, to create a diluent gas flow and a flow of said reactive radicals, with said  
14 flow of said reactive radicals traversing said output aperture toward said mixing manifold and  
15 said flow of gas traveling from said supply to said mixing manifold, with said diluent gas flow  
16 and said flow of said reactive radicals combining when traveling between said inlets and said

17 outlet forming a gas-radical mixture egressing from said outlet and traversing through said  
18 intake port;

19 a controller configured to regulate said pump system and said plasma source;

20 and

21 a memory, coupled to said controller, comprising a computer-readable medium  
22 having a computer-readable program embodied therein for directing operation of said substrate  
23 processing system, said computer-readable program including a set of computer instructions to  
24 be operated on by said controller to regulate the introduction of said radicals from said plasma  
25 into said mixing manifold, said set of computer instructions including:

26 a first subroutine to be operated on by said controller to regulate said pump  
27 system to introduce said reactive radicals into said mixing manifold at a first rate [to] and said  
28 diluent gas at a second rate so as to maintain a pressure with said chamber less than one torr.

1 17. The apparatus of claim 16 wherein said first rate is in the range of 200  
2 and 400 sccm and said second rate is in the range of 500 and 800 sccm.

1 18. The apparatus of claim 16 further including a gas delivery system in  
2 fluid communication with said plasma applicator to transmit a reactive gas thereto, with said  
3 controller being configured to regulate gas delivery system, wherein said set of computer  
4 instructions further includes a second subroutine instructions to be operated on by said  
5 controller to regulate said gas delivery system to introduce said reactive gas at a first rate to  
6 said gas inlet during a first time period at a first flow rate; a third subroutine of computer  
7 instructions for controlling said pump system to maintain a pressure of about 1-20 torr within  
8 said applicator during said first time period.

1 19. The apparatus of claim 16 further including a microwave source in  
2 electrical communication with said plasma applicator, with said controller being configured to  
3 regulate said microwave source, wherein said set of computer instructions further includes a  
4 fourth subroutine to be operated on by said controller to regulate said microwave source to  
5 direct microwaves into said internal volume of said applicator during said first time period.